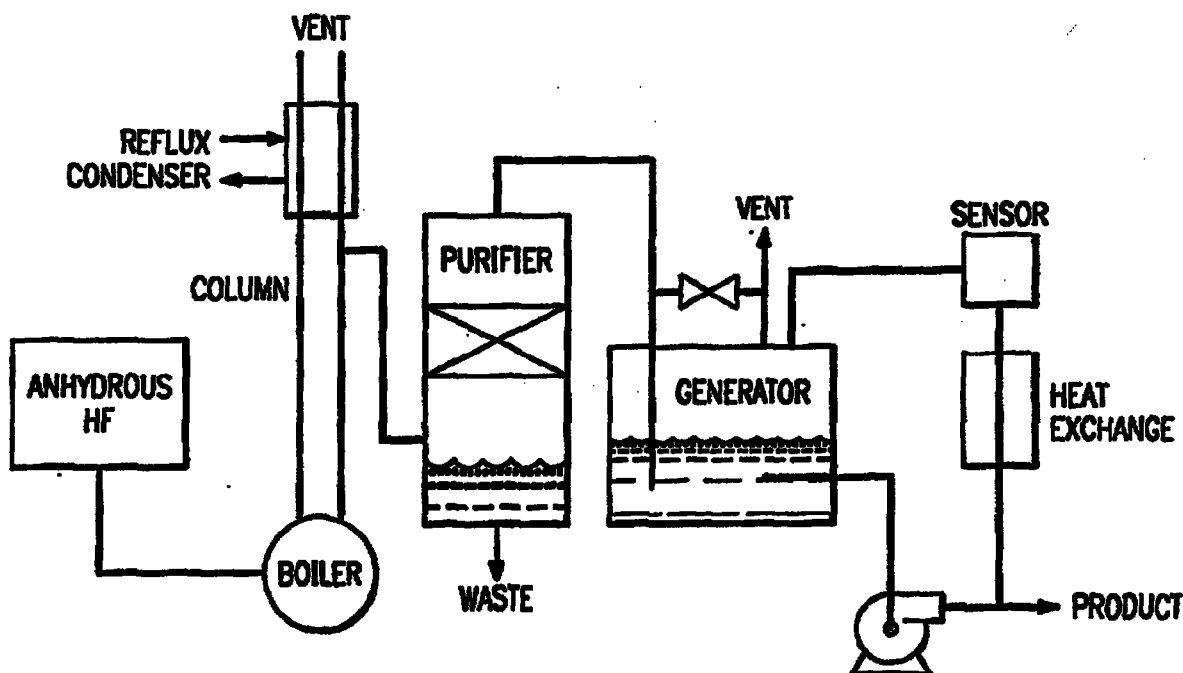


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(54) Title: ON-SITE MANUFACTURE OF ULTRA-HIGH-PURITY HYDROFLUORIC ACID FOR SEMICONDUCTOR PROCESSING**(57) Abstract**

A system for purification and generation of hydrofluoric acid on-site at a semiconductor device fabrication facility. An evaporation stage (optionally with arsenic oxidation) is followed by a fractionating column to remove most other impurities, an Ionic Purifier column to suppress contaminants not removed by the fractionating column, and finally the HF Supplier (HFS).